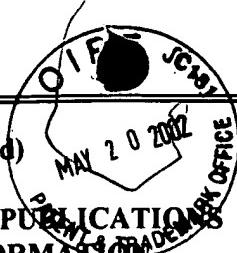


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Jack O. Chu et al.FILING DATE:
October 19, 2000

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REFERENCE DESIGNATION

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EK	AA	6,059,895	05/09/2000	Chu et al.	148	33.1	May 13, 1999
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							YES	NO
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Ak	XP-002111024, "Epitaxial Si-Ge Etch Stop Layers With Ethylene Diamine Pyrocatechol For Bonded And Etchback Silicon-On-Insulator", D. Feijoo et al., AT&T Bell Laboratories, Murray Hill, NJ 07974, revised February 2, 1994.
AM	

EXAMINER *Eric K. Chu*DATE CONSIDERED *7/15/03*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.